


<div>Search Notes</div> <div></div>	Application/Control No.	Applicant(s)/Patent under Reexamination	
	10/710,843	LIN ET AL.	
	Examiner	Art Unit	
	Jae Lee	2823	

SEARCHED			
Class	Subclass	Date	Examiner

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner

SEARCH NOTES (INCLUDING SEARCH STRATEGY)		
	DATE	EXMR
EAST search: searched for reactive ion etching obviousness	8/6/2007	JML